

# The role of the singlet metastables in capacitively coupled oxygen discharges

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# Introduction

- Oxygen is a weakly electronegative gas and the presence of negative ions has a strong influence on the kinetics and dynamics of the oxygen discharge
- The oxygen discharge is of vital importance in various materials processing applications such as
  - ashing of photoresist
  - etching of polymer films
  - oxidation and deposition of thin film oxides
- The oxygen chemistry is rather involved, in particular due to the presence of metastable molecular and atomic oxygen and their role in dissociative attachment and detachment processes



- The 1D particle-in-cell/Monte Carlo collision simulation
- The oxygen discharge
- Capacitively Coupled Oxygen Discharge at 13.56 MHz
  - Pressure dependence – including  $O_2(a^1\Delta_g)$
  - Including both  $O_2(a^1\Delta_g)$  and  $O_2(b^1\Sigma_g)$
  - Including secondary electron emission
- Summary



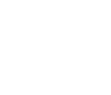
# The 1D particle-in-cell/Monte Carlo collision simulation



# The *oopd1 1d-3v PIC/MCC code*

- We use the `oopd1` (objective oriented plasma device for one dimension) code to simulate the discharge
- The `oopd1` code was originally developed at the Plasma Theory and Simulation Group at UC Berkeley
- It has 1 dimension in space and 3 velocity components for particles (1d-3v)
- The `oopd1` code is supposed to replace the widely used `xpdx1` series (`xpdp1`, `xpdc1` and `xpds1`)
- It is developed to simulate various types of plasmas, including processing discharges, accelerators and beams
  - Modular structure
  - Includes relativistic kinematics
  - Particles can have different weights

# The oxygen discharge



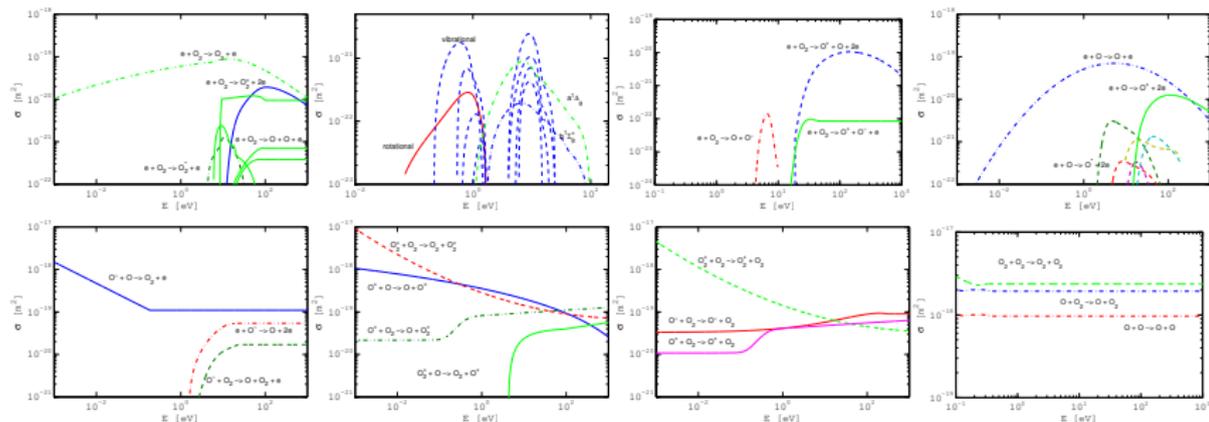
# The oxygen discharge

- We consider a discharge that consists of:
  - electrons
  - the ground state oxygen molecule  $O_2(X^3\Sigma_g^-)$
  - the metastable oxygen molecule  $O_2(a^1\Delta_g)$
  - the metastable oxygen molecule  $O_2(b^1\Sigma_g)$
  - the ground state oxygen atom  $O(^3P)$
  - the metastable oxygen atom  $O(^1D)$
  - the negative oxygen ion  $O^-$
  - the positive oxygen ions  $O^+$  and  $O_2^+$
- We apply a global model<sup>1</sup> beforehand to calculate the partial pressure of the various neutrals

<sup>1</sup> Thorsteinsson and Gudmundsson, *Plasma Sources Sci. Technol.*, **19** 055008 (2010)



# The oxygen discharge



- The reaction set for the oxygen is comprehensive and for this study includes 67 reactions

Gudmundsson et al., *Plasma Sources Sci. Technol.*, **22** 035011 (2013), and **24** 035016 (2015)



# Capacitively Coupled Oxygen Discharge at 13.56 MHz – pressure dependence – including $O_2(a^1\Delta_g)$



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

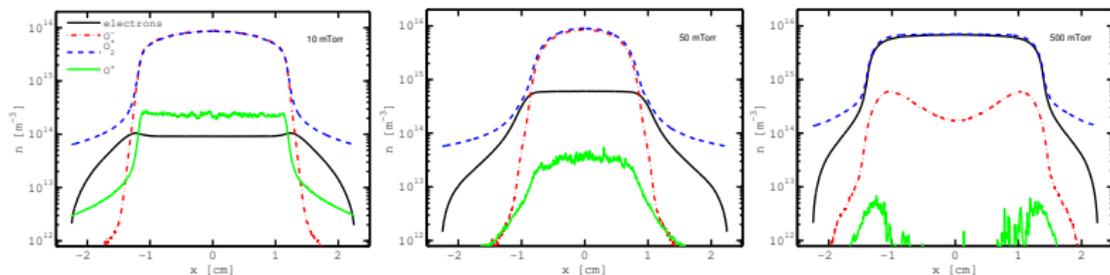
- We apply a voltage source with a single frequency

$$V(t) = V_{\text{rf}} \sin(2\pi ft)$$

- The electrodes are circular with a diameter of 14.36 cm
- The gap between the electrodes is 4.5 cm
- We set  $V_{\text{rf}} = 222$  V and  $f = 13.56$  MHz
- The neutrals ( $\text{O}_2$  and  $\text{O}$ ) are treated as background gas at  $T_{\text{g}} = 300$  K with a Maxwellian distribution
- The dissociation fraction and the metastable fraction is found using a global model
- The pressure is varied from 10 – 500 mTorr

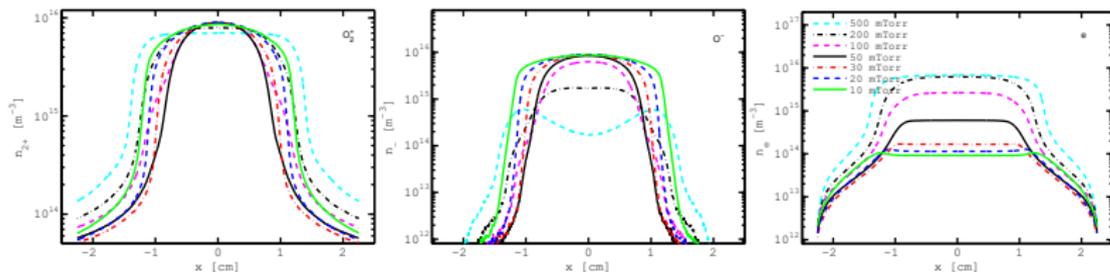


# Capacitively Coupled Oxygen Discharge at 13.56 MHz



- For a parallel plate capacitively coupled oxygen discharge at 50 mTorr with a gap separation of 4.5 cm by a 222 V voltage source at 13.56 MHz
  - $\text{O}_2^+$ -ion density profile
  - $\text{O}^+$ -ion density profile
  - $\text{O}^-$ -ion density profile
  - electron density profile

# Capacitively Coupled Oxygen Discharge at 13.56 MHz



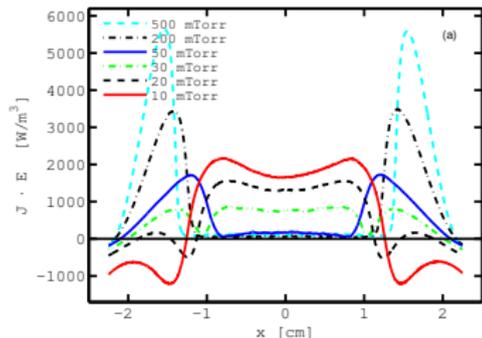
- The sheath width decreases as the pressure is decreased in the pressure range from 50 mTorr to 10 mTorr
- The sheath widths are largest at 50 mTorr
- As the pressure is increased from 50 mTorr up to 500 mTorr the sheath width decreases
- This agrees with what has been observed experimentally in the pressure range 40 – 375 mTorr

Mutsukura et al. (1990) JAP **68** 2657 and van Roosmalen et al. (1985) JAP **58** 653



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- The electron heating profile  $\mathbf{J_e \cdot E}$
- In the pressure range 50 - 500 mTorr the electron heating occurs almost solely in the sheath region
- As the pressure is decreased the Ohmic heating contribution in the plasma bulk increases and sheath heating decreases

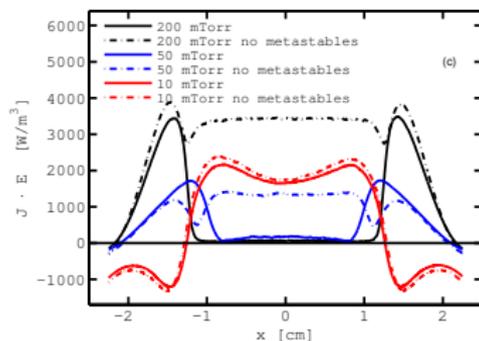


Gudmundsson and Ventéjou (2015) JAP **118** 153302



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- At 10 mTorr excluding the metastable states in the simulation has very small influence on the heating mechanism
- At 50 mTorr the metastable states have a significant influence on the heating mechanism
- The role of the metastables is even more significant at 200 mTorr



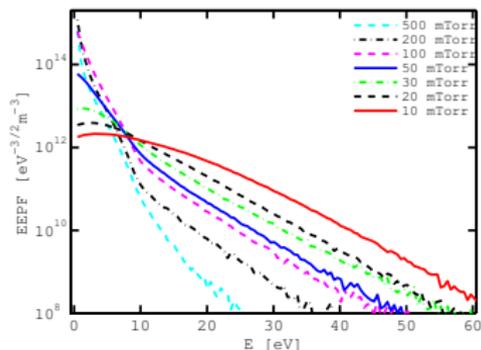
Gudmundsson and Ventéjou (2015) JAP **118** 153302

Gudmundsson and Lieberman (2015) PSST **24** 035016



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- At low pressure the EEPF is convex, the population of low energy electrons is relatively low
- As the pressure is increased the number of low energy electrons increases and the number of higher energy electrons ( $> 10$  eV) decreases
- Thus the EEPF develops a concave shape or becomes bi-Maxwellian as the pressure is increased

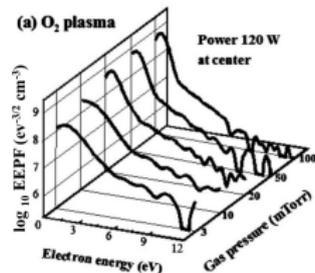


Gudmundsson and Ventéjou (2015) JAP **118** 153302

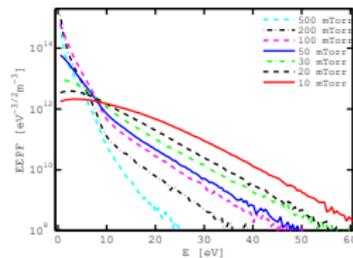


# Capacitively Coupled Oxygen Discharge at 13.56 MHz

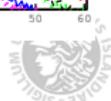
- Our results agree with the measurements of Lee et al. (2010) which explored experimentally the evolution of the EEPF with pressure in a capacitively coupled oxygen discharge in the pressure range 3 – 100 mTorr
- They find that the EEPF became more distinctly bi-Maxwellian and the density of low energy electrons increases as the gas pressure is increased



Lee et al. (2010) PRE **81** 046402

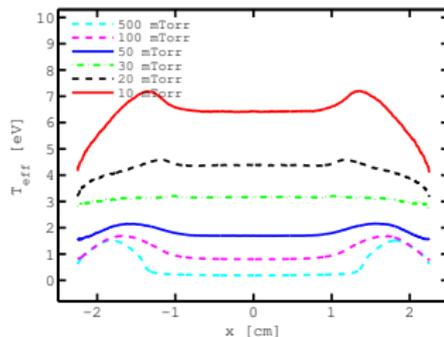


Gudmundsson and Ventéjou (2015) JAP **118** 153302



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- The effective electron temperature drops as the pressure is increased
- We had seen earlier that when the metastable singlet oxygen molecule  $O_2(a^1\Delta_g)$  is added to the discharge model the effective electron temperature drops, in particular in the electronegative core



Gudmundsson and Ventéjou (2015) JAP **118** 153302

Gudmundsson and Lieberman (2015) PSST **24** 035016



# Capacitively Coupled Oxygen Discharge at 13.56 MHz – pressure dependence – including $O_2(a^1\Delta_g)$ and $O_2(b^1\Sigma_g)$

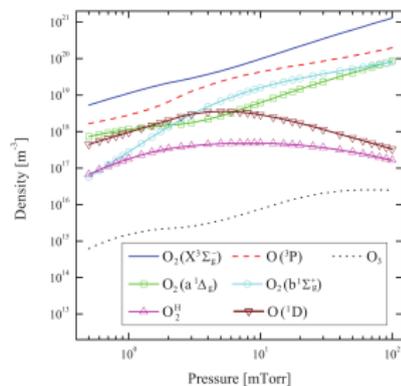


# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- It has been known for decades that the metastable oxygen molecule  $O_2(b^1\Sigma_g)$  plays an important role in the oxygen discharge

Thompson (1961) *Proc. Royal Soc. A* 262(1311) 519

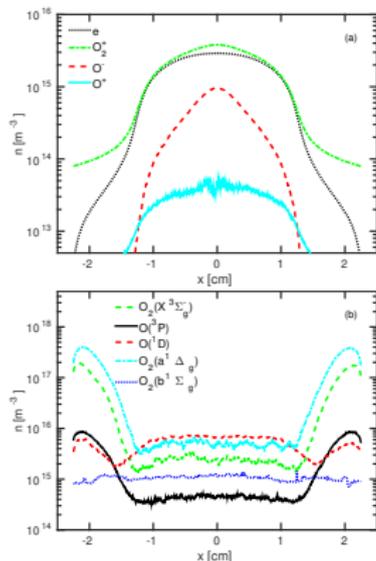
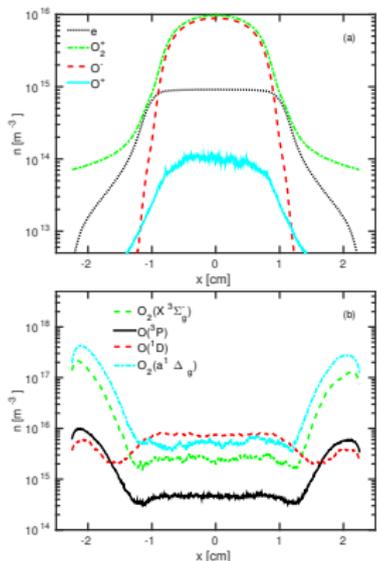
- Recent global model study indicates there is a significant density of  $O_2(b^1\Sigma_g)$  in the oxygen discharge
- The  $O_2(b^1\Sigma_g)$  is mainly created through



Toneli et al., *J. Phys. D*, **48** 325202 (2015)



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

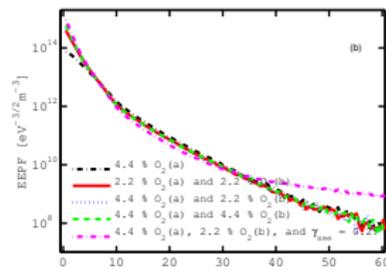
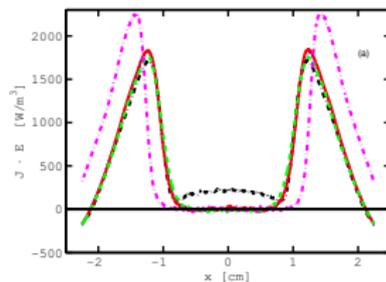


- The density profiles of charged particles and fast neutrals comparing including  $\text{O}_2(a^1\Delta_g)$  (left) and  $\text{O}_2(a^1\Delta_g)$  and  $\text{O}_2(b^1\Sigma_g)$  (right) at 50 mTorr



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- The number of cold electrons increases as  $O_2(b^1\Sigma_g)$  is added to the discharge model
- The electron heating in the bulk drops to zero
- The EEPF is roughly independent of the partial pressure of  $O_2(a^1\Delta_g)$  and  $O_2(b^1\Sigma_g)$  while both are included
- Adding secondary electron emission ( $\gamma_{see} = 0.2$ ) leads to a high energy tail in the EEPF

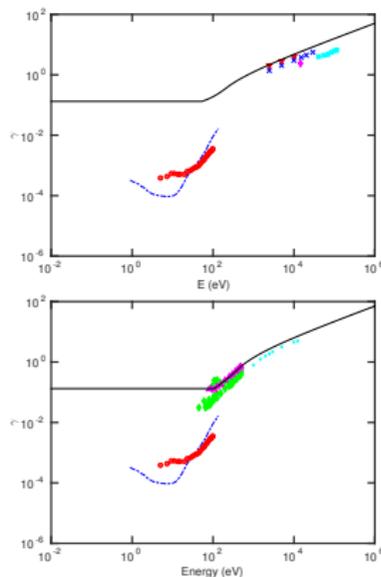


# Capacitively Coupled Oxygen Discharge at 13.56 MHz – including secondary electron emission

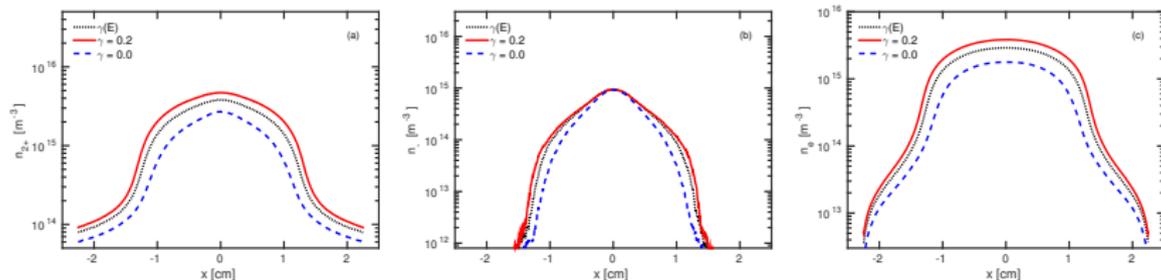


# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- We have compiled experimental data from the literature on secondary electron emission yields for the species  $O_2^+$ ,  $O^+$ ,  $O_2$  and  $O$  bombarding various metals and substances
- A fit was made through the available experimental data



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

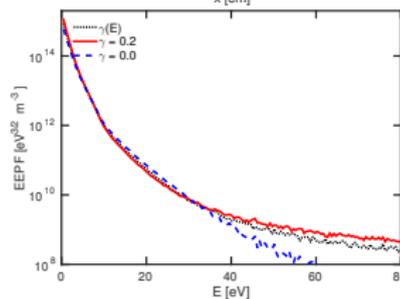
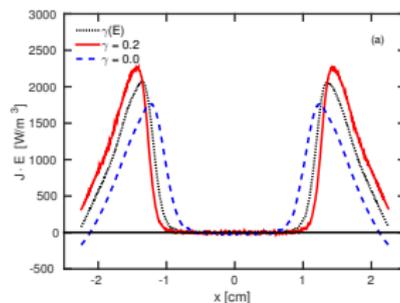


- The  $\text{O}_2^+$ ,  $\text{O}^-$  and electron density profiles for  $\gamma_{\text{see}} = 0.0$ ,  $\gamma_{\text{see}} = 0.2$ , and energy dependent secondary electron emission yield
- The electron density increases with increased secondary electron emission yield



# Capacitively Coupled Oxygen Discharge at 13.56 MHz

- Increased secondary electron emission yield increases the electron heating rate in the sheath region and the sheath region becomes narrower



# Summary



# Summary

- We explored a capacitively coupled oxygen discharge using particle-in-cell/Monte Carlo collision simulation
- The reaction set includes
  - Oxygen atoms  $O(^3P)$  and  $O^+$ -ions
  - The metastables  $O(^1D)$ ,  $O_2(a^1\Delta_g)$  and  $O_2(b^1\Sigma_g)$
- At low pressure the EEPF is convex and develops a concave shape or becomes bi-Maxwellian as the pressure is increased
- These results contradict what is commonly found for the capacitively coupled argon discharge where the EEPF evolves from being concave at low pressure to being convex at high pressure



# Thank you for your attention

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  - US Department of Energy Office of Fusion Energy Science Contract DE-SC000193
  - A gift from the Lam Research Corporation

The slides can be downloaded at

<http://langmuir.raunvis.hi.is/~tumi/plasma.html>



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